Electronic Supplementary Material (ESI) for RSC Advances.

Atmospheric-pressure Microplasma as Anode for Rapid and Simple Electrochemical Deposition of Copper and Cuprous Oxide Nanostructures

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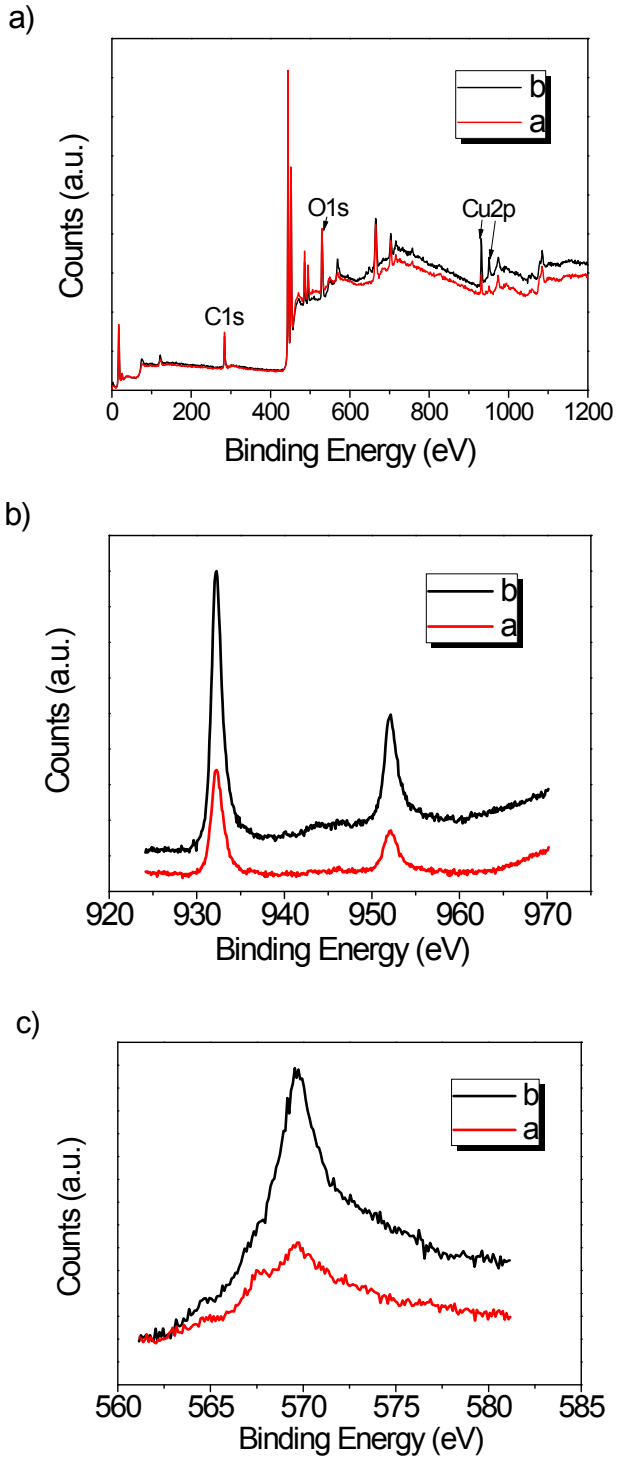

Figure S1. XPS data of nanoparticles deposited on ITO cathodes at different conditions. a) Survey spectra, b) Cu 2p, c) Cu LMM Auger spectra. a. 25℃, 1 M $CuSO_4$ and b. 70℃, 100 mM $CuSO_4$. The discharge current is 6 mA and discharge time is 120s.

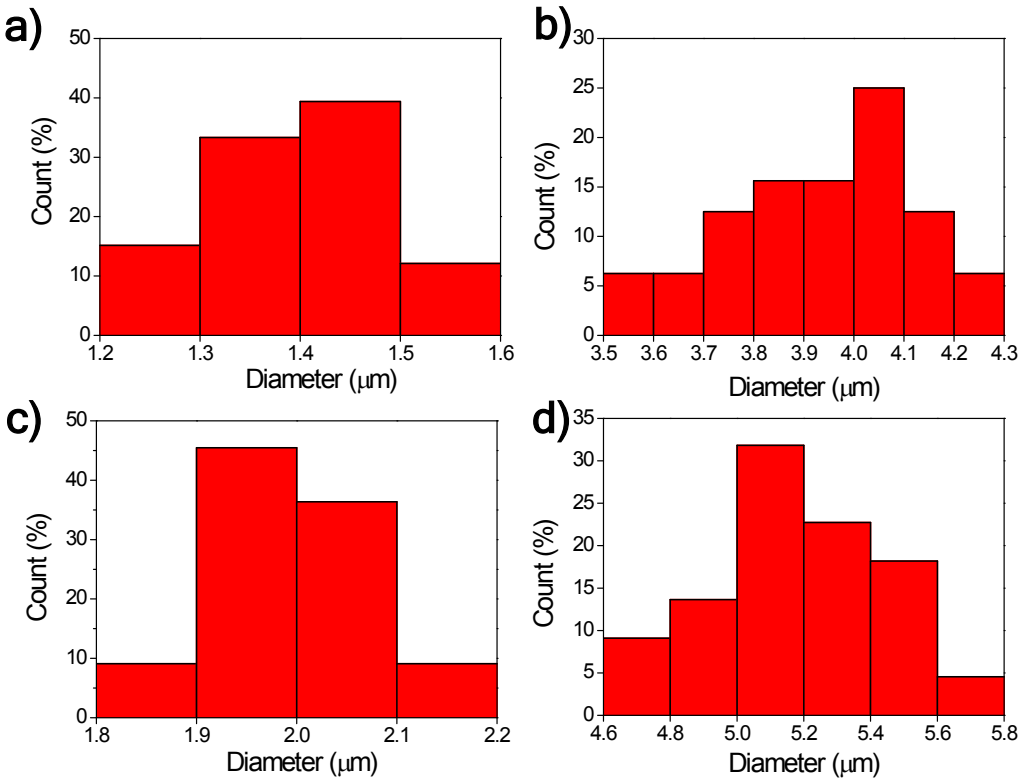

Figure S2. Size distribution of nanoparticles deposited on ITO cathodes at different conditions. 25℃, 1 M $CuSO_4$ with discharge time of a) 5 s and b) 120s. 70℃, 100 mM $CuSO_4$ with discharge time of c) 5 s and d) 120s. The discharge current is 6 mA.